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(54) Title: LITHOGRAPHIC PROJECTION APPARATUS, GAS PURGING METHOD, DEVICE MANUFACTURING METHOD AND PURGE GAS SUPPLY SYSTEM

(57) Abstract: A lithographic projection apparatus includes a support configured to support a patterning device, the patterning device configured to pattern the projection beam according to a desired pattern. The apparatus has a substrate table configured to hold a substrate, a projection system configured to project the patterned beam onto a target portion of the substrate. The apparatus also has a purge gas supply system configured to provide a purge gas near a surface of a component of the lithographic projection apparatus. The purge gas supply system includes a purge gas mixture generator configured to generate a purge gas mixture which includes at least one purging gas and moisture. The purge gas mixture generator has a moisturizer configured to add the moisture to the purge gas and a purge gas mixture outlet connected to the purge gas mixture generator configured to supply the purge gas mixture near the surface.

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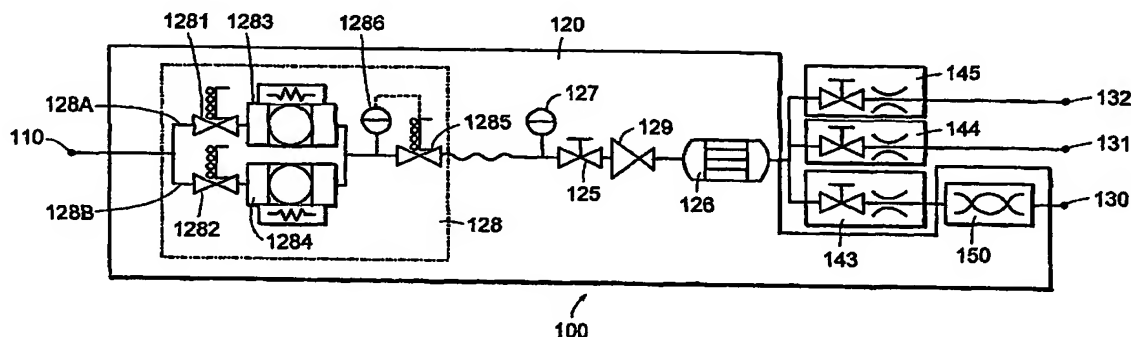
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ning of each regular issue of the PCT Gazette.

(54) Title: **LITHOGRAPHIC PROJECTION APPARATUS, PURGE GAS SUPPLY SYSTEM AND GAS PURGING**



(57) Abstract: A lithographic projection apparatus (1) includes a support configured to support a patterning device (MA), the pat-
tarning device configured to pattern the projection beam according to a desired patter. The apparatus has a substrate (W) table
configure to hold a substrate, a projection system configured to project the patterned beam onto a target portion of the substrate. The
apparatus also has a purge gas supply system (100) configured to provide a purge gas near a surface of a component of the lithogra-
phic projection apparatus. The purge gas supply system (100) includes a purge gas mixture generator (120) configured to generate
a purge gas mixture which includes at least one purging gas and moisture. The purge gas mixture generator has a moisturizer (150)
configured to add the moisture to the purge gas and a purge gas mixture outlet (130) connected to the purge gas mixture generator
(120) configured to supply the purge gas mixture near the surface.